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(54) Title: UNDERLAYER COATING COMPOSITION AND PROCESS FOR MANUFACTURING A MICROELECTRONIC DEVICE

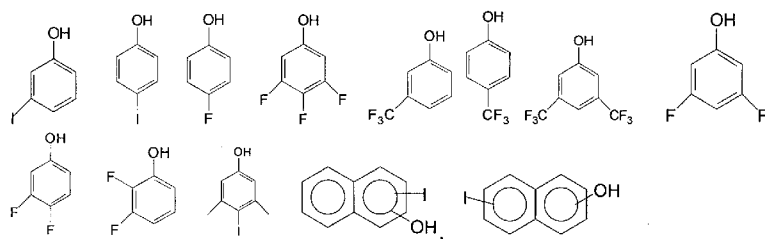


Figure 1: Examples of the phenolic monomer

(57) Abstract: The invention relates to an underlayer coating composition comprising a polymer, where the polymer comprises at least one hydroxyaromatic unit in the backbone of the polymer phenol which has a pendant group comprising a fluoro or iodo moiety, and at least one unit comprising an aminoplast. The invention further relates to a process for forming an image using the composition, especially for EUV.